2016 International Workshop on EUV Lithography
(2016 EUVL Workshop)

June 13-16, 2016 ▪ CXRO · LBL· Berkeley, CA

Wednesday, June 15, 2016

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2016 EUVL Workshop

Organized by

Promoting EUV Lithography via Workshops, Consulting and Education

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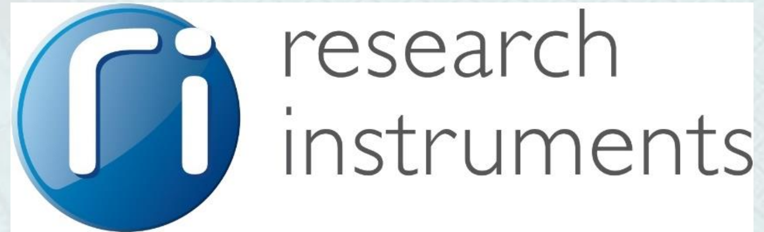

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Building 66
Building 54
Reception and Poster Session
Lawrence Hall of Science
Grizzly Peak Gate
Strawberry Canyon Gate
Blackberry Canyon Entrance

Announcements

- Speaker Timer – let us stay on time!
  - Green – OK
  - Yellow –Q&A time started
  - Red – Time Over
- Hand held reminder signs: 5, 2 and Time Over
- Keynote talks – 35 minutes plus 5 min. Q & A
- Oral presentations – 17 minutes 3 min. Q & A
- Reserved seat for speakers and session co-chairs

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Announcements

- EUVL Survey
  - This year we have an audience survey on Thursday afternoon, at the end of the meeting
  - If you are leaving today, please complete the survey (located at the registration desk) and leave it with Juanita

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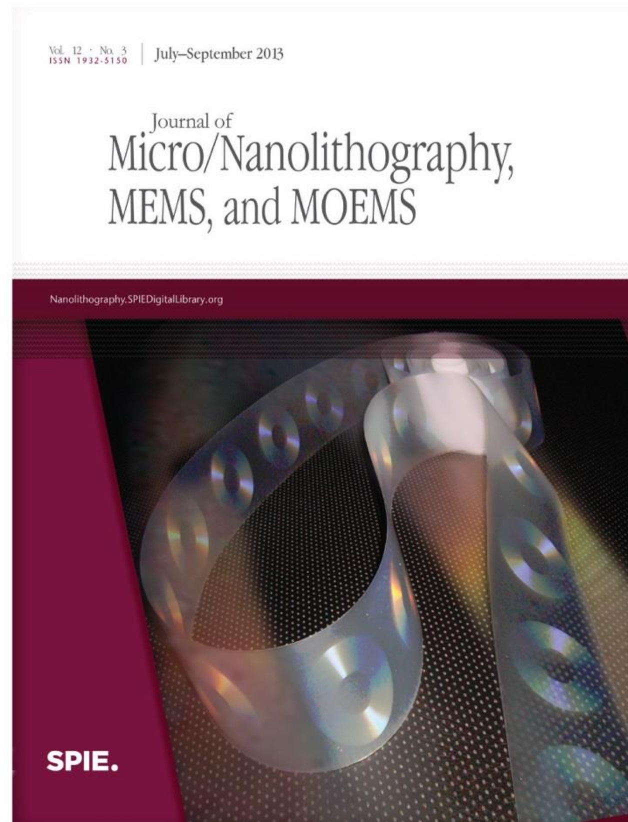
SPIE

Submit your work to the *Journal of Micro/Nanolithography, MEMS, and MOEMS*



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Where to find JM^3 on the web

- Information about the journal, information for contributors, etc :
  - http://spie.org/x865.xml
- Submit a manuscript: http://jm3.msubmit.net/cgi-bin/main.plex
- Browse, read, and download articles from the SPIE digital library:
  - http://nanolithography.spiedigitallibrary.org/journal.aspx
- **Pleas contact Vivek Bakshi, if you have any questions or need help in submission of your manuscript**

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WORKSHOP AGENDA

- **8:55 AM …Session 1: Keynote Presentations**
- **9:05 AM …Session 1: Keynote Presentations**
- **10:25 AM ……………………..Break (15 Minutes)**
- **10:40 AM……………… Session 2: EUV Sources**
- **12:00 PM……………………………………Lunch**

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WORKSHOP AGENDA

- **1:00 PM…………..Session 3: FEL based EUV Sources**
- **2:00 PM ………..Break and Group photograph (30 Minutes)**
- **2:30 PM……………………..Session 4: EUV Optics**
- **4:30 PM……………………….Adjourn for the day for Networking**

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